

FORM PTO-1449

INFORMATION DISCLOSURE
CITATION IN AN APPLICATION

JAN 28 2005

DOCKET NUMBER
DSI 302 ✓APPLICATION NUMBER
~~10/815,994~~ 10/816,179APPLICANTS
Chung J. Lee et al.FILING DATE
March 31, 2004GROUP ART UNIT
~~2827~~ 1763

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.
12A	3,268,599	08/23/1966	Chow	↑	144	
	3,274,267	09/20/1966	Chow	↑	129	
	3,280,202	10/18/1966	Gilch	570	144	
	3,288,728	11/29/1966	Gorham	↑	86	
	3,332,891	07/25/1967	Chow et al.	↑	391	
	3,342,754	09/19/1967	Gorham et al.	↑	386	
	3,349,045	10/24/1967	Gilch	528	397	
	3,379,803	04/23/1968	Tittmann et al.	264	81	
✓	3,503,903	03/31/1970	Shaw et al.	528	386	

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DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES NO
10 EP 0 349 032 A2	01/03/1990	EPO			
EP 0 523 479 A2	01/20/1993	EPO			
✓ EP 0 856 503 A1	08/05/1998	EPO			

OTHER DOCUMENTS

12A	Chow et al., <i>Poly (a,a,a',a'-tetrafluoro-p-xylylene)</i> , <u>Journal of Applied Polymer Science</u> , Vol. 13, No. 9, pp. 2325-2332, 1969.
	Chow et al., <i>The Synthesis of 1,1,2,2,9,9,10,10-octafluorou2, 2Paracyclophane</i> , <u>Journal of Organic Chemistry</u> , Vol. 35, No. 1, pp. 20-22, 1970.
✓	Iwamoto et al., <i>Crystal Structure of Poly-p-xylylene. I. The a Form</i> , <u>Jour. Polymer. Sci. Polymer. Phys. Ed.</u> , Vol. 11, pp. 2403-2411, 1973.

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11/6/5

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RD ↓	3,509,075	04/28/1970	Niegish et al.	528	396	
	3,626,032	12/07/1971	Norris	526	75	
	3,694,495	09/26/1972	Norris	302	496	
	3,940,530	02/24/1976	Loeb et al.	428	206	
	4,117,308	09/26/1978	Boggs et al.	392	360	
	4,518,623	05/21/1985	Riley	427	8	
	4,823,711	04/25/1989	Kroneberger et al.	110	236	
	4,996,010	02/26/1991	Modrek	264	401	
	5,142,023	08/25/1992	Gruber et al.	528	354	
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	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES NO
RD ↓	GB 650 947	03/07/1951	Great Britain			
	GB 673 651	06/11/1952	Great Britain			
	WO 97/15699	05/01/1997	WIPO			
OTHER DOCUMENTS						
	Iwamoto et al., <i>Crystallization During Polymerization of Poly-p-xylene. III. Crystal Structure and Molecular Orientation as a Function of Temperature</i> , <u>Journal of Polymer Science Polymer. Phys. Ed.</u> , Vol. 13, pp. 1925-1938, 1975.					
RD	Lee, <i>Transport Polymerization of Gaseous Intermediates and Polymer Crystal Growth</i> , <u>J. Macromol. Sci. Rev. Macromol. Chem.</u> , C16(1), p. 79-127, 1977-78.					
↓	Sharma et al., <i>Optimizing Poly(chloro-p-Xylylene) or Parylene C Synthesis</i> , <u>Journal of Applied Science</u> , Vol. 36, No. 7, pp. 1555-1565, Sept. 20, 1988.					
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10	5,217,559	06/08/1993	Moslehi et al.	132	345.35	
	5,268,202	12/07/1993	You et al.	427	25.6	
	5,320,518	06/14/1994	Stilger et al.	431	7	
	5,475,080	12/12/1995	Gruber et al.	528	354	
	5,482,009	01/09/1996	Kobayashi et al.	122	367.1	
	5,538,758	07/23/1996	Beach et al.	427	25.6	
	5,572,884	11/12/1996	Christensen et al.	62	476	
	5,639,512	06/17/1997	Nonaka et al.	427	163.2	
✓	5,648,006	07/15/1997	Min et al.	219	444.1	

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	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES NO
10	WO 97/15951	05/01/1997	WIPO			
	WO 97/42356	11/13/1997	WIPO			
✓	WO 99/21705	05/06/1999	WIPO			

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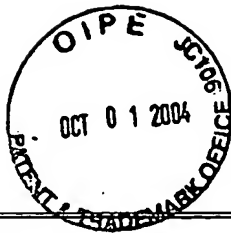
10	Lee, <i>Polyimides, Polyquinolines and Polyquinoxalines: Tg-Structure Relationships</i> , <u>Journal of Macromolecular Science, Part C - Polymer Reviews</u> (formerly <u>Journal of Macromolecular Science, Part C - Reviews in Macromolecular Chemistry and Physics</u>) Vol. 29(4), p. 431, 1989.
	Lang, <i>Vapor Deposition of Very low k Polymer Films, Poly (Naphthalene), Poly (Fluorinated Naphthalene)</i> , <u>Materials Research Society Symposium Proceedings</u> , Vol. 381, pp. 45-50, April 17, 1995.
✓	Wary et al., <i>Polymer Developed to be Interlayer Dielectric</i> , <u>Semi-Conductor International</u> , pp. 211-216, June 1996.

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EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.	
JL	5,879,808	03/09/1999	Wary et al.	428	411.1		
	5,945,170	08/31/1999	Kozak et al.	427	437		
	5,958,510	09/28/1999	Sivaramakrishnam	427	255.6		
	6,051,321	04/18/2000	Lee et al.	428	411.7		
	6,130,171	10/10/2000	Gomi	438	781		
	6,140,456	10/31/2000	Foggiator	528	196		
	6,144,802	11/07/2000	Kim	392	479		
	6,265,320	07/24/2001	Shi et al.	438	728		
	✓	6,302,874	10/16/2001	Zhang	604	522	
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	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES NO	
JL	WO 99/21706	05/06/1999	WIPO				
	WO 99/21924	05/06/1999	WIPO				
	✓	WO 99/22043	05/06/1999	WIPO			
OTHER DOCUMENTS							
JL	Wunderlick, <i>Crystal Nucleation, Growth, Annealing, Macromolecular Physics</i> , Vol. 1-2, pp. 242-243, 246-247, 1996.						
	Greiner, <i>Poly(1,4-xylylene)s: Polymer Films by Chemical Vapour Deposition, Trends in Polymer Science</i> , Vol. 5, No. 1, pp. 12-16, 1997.						
	Harrus et al., <i>Parylene Af-4: A Low ϵ_r Material Candidate for ULSI Multilevel Interconnect Applications</i> , <i>Material Research Society Symposium Proceedings</i> , Vol. 443, 1997.						
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		APPLICANTS Chung J. Lee et al.				
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EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.
	6,703,462	03/09/2004	Lee	526	242	
	6,797,343	09/28/2004	Lee	428	1.1	
	2002/0050659	05/02/2002	Toreki et al.	264	4.1	
	2002/0120083	08/29/2002	Lee	526	242	
	2003/0051662	03/20/2003	Lee	118	50	
	2003/0072947	04/17/2003	Lee	428	421	
	2003/0143341	07/31/2003	Lee	428	1.1	
	2003-0188683	10/9/2003	Lee	118	52.1	
	2003-0195312	10/16/2003	Lee	526	242	
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	Plano et al., <i>The Effect of Deposition Conditions on the Properties of Vapor-Deposited Parylene Af-4 Films</i> , <u>Material Research Society Symposium Proceedings</u> , Vol. 476, pp. 213-218, 1997.					
	Ryan et al., <i>Effect of Deposition and Annealing on the Thermomechanical Properties of Parylene Films</i> , <u>Material Research Society Symposium Proceedings</u> , Vol. 476, pp. 225-230, 1997.					
	Yang et al., <i>High Deposition Rate Parylene Films</i> , <u>Journal of Crystal Growth</u> , Vol. 183, No. 3, pp. 385-390, 1998.					
	Mathur et al., <i>Vapor Deposition of Parylene-F Using Hydrogen as Carrier Gas</i> , <u>Journal of Materials Research</u> , Vol. 14, No. 1, pp. 246-250, 1999.					
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SHEET 1 OF 1

FORM PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION	DOCKET NUMBER DSI 302	APPLICATION NUMBER 10/816,179
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<i>Be</i>	3,503,903	3/31/70	Shaw et al.	528	396	
	6,086,952	7/11/00	Lang et al.	427	255.29	
	6,130,171	10/10/00	Gomi		781	
	6,265,320	7/24/01	Shi et al.		725	
	6,455,443	9/24/02	Eckert et al.	438	781	
<i>✓</i>	6,495,208	12/17/02	Desu et al.	427	255.31	

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	<i>Parylene Copolymers</i> , Taylor et al., <i>Low Dielectric Constant Materials III</i> , pp. 197-205, 1997.
<i>Be</i>	<i>Finer Copper Wires Make for Faster Integrated Circuits</i> , Preuss, <i>Research News</i> , pp. 1-3, April 5, 1999.
	<i>Study of Hydrogen Annealing of Ultrahigh Molecular Weight Polyethylene Irradiated with High-Energy Protons</i> , Wilson et al., <i>Journal of Materials Research</i> , Vol. 14, No. 11, November 1999.
	<i>A Novel Oxazole Based Low k Dielectric Addresses Copper Damascene Needs</i> , Schmid et al., <i>Semiconductor Fabtech</i> , 12 th Edition, pp. 231-235, July 2000.
	<i>The Effect of Water Desorption and Organosilane Coupling Agents on the Adhesion of Poly(p-xylylene) Films to a Silicon Wafer Surface</i> , Lightfoot et al., <i>Journal of Materials Science: Materials in Electronics</i> , Vol. 12, pp. 581-586, 2001.
<i>✓</i>	<i>Current Technical Trends: Dual Damascene & Low-k Dielectrics</i> , Healey on behalf of Threshold Systems, pp. 1-6, © 2002.

EXAMINER <i>[Signature]</i>	DATE CONSIDERED <i>11/26/05</i>
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